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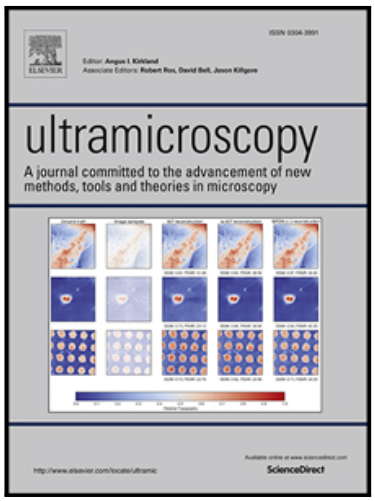


# Low-Energy Electron Potentiometry

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PII: S0304-3991(16)30285-6
DOI: 10.1016/j.ultramic.2017.05.015
Reference: ULTRAM 12382

To appear in: *Ultramicroscopy*

Received date: 28 December 2016
Revised date: 21 April 2017
Accepted date: 9 May 2017

Please cite this article as: Johannes Jobst, Jaap Kautz, Maria Mytiliniou, Rudolf M. Tromp, Sense Jan van der Molen, Low-Energy Electron Potentiometry, *Ultramicroscopy* (2017), doi: 10.1016/j.ultramic.2017.05.015

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**Highlights**

- Electronic properties of surfaces are mapped out by low-energy electron microscopy
- High lateral resolution, a large field of view and fast data acquisition is achieved
- Virtually, any sample can be studied using low-energy electron potentiometry
- Intrinsic, lateral workfunction variations are studied in detail
- Lateral properties of Schottky contacts on metal-silicon interfaces are resolved

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